

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

1-20 (Canceled)

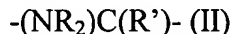
21. (New) A process for producing a fluorinated and silylated derivative exhibiting a bond between a carbon carrying at least one fluorine and a silicon, comprising the step of reacting a derivative of formula (I)  $R_f-Y-O-D$  with a base, wherein in said formula (I):

$R_f$  represents a hydrocarbon group having from 1 to 15 carbon atoms having at least one fluorine atom on the carbon in the  $\alpha$  position with respect to Y,

D is a silylated radical, and

Y is chosen a carbonyl or an aminoalkylene group.

22. (New) The process as claimed in claim 21, wherein Y is an aminoalkylene of formula:



where the two R groups, which are identical or different, are such that  $HNR_2$  is an optionally cyclic secondary amine of at most 10 carbon atoms and wherein  $R'$  is hydrogen or an aliphatic radical or aromatic radical of at most 10 carbon atoms, optionally of at most 6.

23. (New) The process as claimed in claim 21, wherein Y is carbonyl.

24. (New) The process as claimed in claim 21, wherein D corresponds to the formula  $\text{Si}(\text{R}_1)(\text{R}_2)(\text{R}_3)$  (III) with  $\text{R}_1$ ,  $\text{R}_2$  and  $\text{R}_3$ , which are identical or different, being aryl, alkyl, alkyloxyl or halogen, optionally chlorine or fluorine.
25. (New) The process as claimed in claim 21, wherein D corresponds to the formula  $\text{Si}(\text{R}_1)(\text{R}_2)(\text{R}_3)$  (III) with  $\text{R}_1$  and  $\text{R}_2$ , which are identical or different, being aryl or alkyl and  $\text{R}_3$  being aryl, alkyl or alkyloxyl radicals.
26. (New) The process as claimed in claim 21, wherein  $\text{R}_f$  represents an hydrocarbon group having from 1 to 10 carbon atoms, optionally from 1 to 4 carbon atoms.
27. (New) The process as claimed in claim 26, wherein  $\text{R}_f$  is trifluoromethyl, pentafluoroethyl, heptafluoropropyls or nonafluorobutyls.
28. (New) The process as claimed in claim 27, wherein  $\text{R}_f$  is trifluoromethyl.
29. (New) The process as claimed in claim 21, wherein the base is a weak base and such that the  $\text{pK}_a$  of the associated acid is at most equal to 7, optionally to 1.
30. (New) The process as claimed in claim 29, wherein the base is a weakly silicophilic basic anion.
31. (New) The process as claimed in claim 30, wherein the base is such that, when 1 mole of trimethylsilyl trifluoroacetate is brought into contact with  $1/10^{\text{th}}$  of an equivalent of basic anions in anhydrous DMF, a silylated ratio (basic anion initially present – free trifluoroacetate)/(free trifluoroacetate) at least equal to  $1/50^{\text{th}}$ , advantageously to  $1/10^{\text{th}}$ , optionally to  $1/2$ , is obtained at thermodynamic equilibrium.

32. (New) The process as claimed in claim 29, wherein the base presents a molar ratio, expressed in equivalents, (numerator) to the derivative of formula (I), of at least equal to 0.005, optionally to 0.02.
33. (New) The process as claimed in claim 32, wherein the molar ratio is at most equal to 2, optionally to 0.2.
34. (New) The process as claimed in claim 21, wherein the reaction is carried out in a medium selected from the group consisting of aprotic solvents, ionic solvents, molten salts and their mixture.
35. (New) The process as claimed in claim 34, wherein the medium has a concentration of acid(s) with a pKa of less than 20, optionally less than 30, of at most equal to 1000 ppm in moles with respect to the moles of solvent(s).
36. (New) The process as claimed in claim 34, wherein the reaction is carried out in a polar aprotic solvent, the donor number DN of which is at least equal to 10, optionally to 20.
37. (New) The process as claimed in claim 36, wherein the polar aprotic solvent has a dielectric constant  $\epsilon$  of at least equal to 10, optionally to 15.
38. (New) The process as claimed in claim 21, wherein the reaction is carried out at a at least equal to atmospheric pressure.
39. A reagent, for successive or simultaneous addition comprising:  
a weak base which is weakly silicophilic;  
a compound of formula (I) Rf-Y-O-D, wherein in said formula (I):

Rf represents a hydrocarbon group having from 1 to 15 carbon atoms

having at least one fluorine atom on the carbon in the  $\alpha$  position with  
respect to Y;

D is a silylated radical;

Y is a carbonyl; and

a solvent, the boiling point of which is at least equal to 100°C, optionally  
from 130°C to 150°C.